



KINTEK SOLUTION

Pecvd Machine Catalog

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KINTEK SOLUTION

COMPANY PROFILE

>>> About Us

Company Profile

Kintek Solution Ltd is one technology orientated organization, team members are devoted to probing the most efficient and reliable technology and innovations in the scientific researching equipment, fields like biochemical reacting, new materials researching, heat treatment, vacuum creating, refrigerating, as well as pharmaceutical and petroleum extracting equipment.

Products & Services

Kintek Solution Ltd is headquartered in Zhengzhou, the capital city of Henan Province, China, and its core business includes the manufacture, distribution and sale of all types of scientific research equipment and laboratory consumables. The wide range of products and services covers the following main areas:

- **Sample Preparation Equipment:** We provide high-performance sample preparation equipment such as tablet presses, ball mills, vibrating sieves and tablet punching machines, which are capable of meeting a wide range of sample preparation needs and ensuring high quality experimental data and research results.
- **Thermal Equipment:** Our thermal equipment includes tube furnaces, sintering furnaces, vacuum furnaces, atmosphere furnaces, graphite furnaces, dental furnaces, rotary furnaces, and high-temperature furnaces (e.g., MPCVD, CVD, PECVD, electric rotary kilns). These facilities excel in high-temperature processing and materials synthesis, meeting a wide range of needs from basic research to industrial production.
- **Biochemical equipment:** We offer a wide range of biochemical laboratory equipment, including rotary evaporators, vacuum pumps, cold trap chillers,

heating circulators, reactors, short-range distillation equipment, sterilization equipment, and homogenizers. These equipments are widely used in the fields of chemical reaction, biological processing and pharmaceutical manufacturing.

- **Laboratory Consumables:** We supply a wide range of laboratory consumables such as fine ceramic products, electrochemical consumables, PTFE material products, high purity materials, battery materials, chemical vapor deposition materials, optical materials, thin film deposition components and glass materials. These consumables provide the necessary support for laboratories to ensure the smooth running of experimental processes.

Technological Advantages

Kintek Solution Ltd has significant technological strengths in the field of scientific research equipment and technical solutions, which enable us to stand out in a competitive marketplace and support our customers with cutting-edge technology. The following are our key technological strengths:

Advanced R&D capabilities

- **Technological Innovation:** Our R&D team is committed to exploring and developing the latest technologies to keep our equipment at the forefront of the industry through continuous technological innovation.
- **Customized solutions:** Based on the specific needs of our customers, we are able to develop and provide customized equipment to meet specific research requirements and application scenarios.
- **Cooperative R&D:** We cooperate with leading research institutes and higher education institutions around the world to carry out R&D projects on cutting-edge technologies to ensure that our technologies are always at the forefront of the industry.

High-performance equipment

- **Precision design:** Our equipment adopts advanced design concepts to ensure high precision, reliability and performance to meet the stringent requirements of scientific research and industrial applications.
- **Advanced materials:** We use high-quality materials and components to improve the durability and stability of our equipment, extend its service life and reduce maintenance costs.

Strict quality control

- Standardized production: All equipment is manufactured in accordance with international quality standards, and each production step is strictly controlled to ensure product consistency and reliability.
- Comprehensive testing: Comprehensive performance testing and quality inspection are carried out before the equipment is delivered to ensure that it meets the customer's technical specifications and operational requirements.

Comprehensive technical support

- Technical Service: Provide comprehensive technical support and after-sales service, including equipment installation, commissioning, training and maintenance, to ensure that customers can use our products efficiently.
- Rapid Response: We have established a rapid response mechanism, which can promptly solve the problems encountered by customers in the process of use and reduce equipment downtime.

Innovative technology integration

- System Integration: We integrate advanced control systems and automation technologies into our equipment to improve operational efficiency and data accuracy, and streamline operational processes.

Through these technological advantages, Kintek Solution Ltd is able to continue to provide our customers with innovative, efficient and reliable scientific research equipment and solutions to promote the continuous progress of scientific research and industrial applications.

Market position and customers

Kintek Solution Ltd is positioned in the market as a leading global provider of high-tech research equipment and solutions, specializing in biochemical reactions, new materials research, heat treatment, vacuum manufacturing, refrigeration, as well as pharmaceuticals and oil extraction. We are committed to brand leadership in research equipment by providing innovative technology and high quality equipment to meet the needs of research organizations and industrial companies in complex research and production processes.

Core Market Positioning:

- **Specialization:** We focus on high technology and scientific research, providing advanced equipment and solutions for specialized research institutes, laboratories and industrial applications.
- **High-end customers:** Our main customers include world-renowned universities, research institutes and various industrial enterprises, which usually have high requirements for equipment performance and technology.
- **Technological Innovation:** We are committed to technological innovation and customized solutions to ensure that our customers receive cutting-edge technical support to meet the ever-changing needs and challenges in the market.

Market Customer Groups:

- **Research Institutes and Universities:** including the world's leading research institutes and institutions of higher learning, who require high-performance research equipment and technical support for basic research, applied research and technology development.
- **Industrial companies:** covering a wide range of industries such as pharmaceuticals, oil extraction, new materials manufacturing and electronic materials production, these companies rely on reliable equipment and solutions to ensure product quality and productivity during production.
- **Laboratories and test centers:** organizations that provide laboratory services and quality testing, requiring accurate laboratory equipment and instruments for sample analysis and testing.
- **Technology Development Companies:** Companies that specialize in the development and application of new technologies and have a high demand for innovative equipment and technical solutions to support their R&D projects and technology validation.

Through clear market positioning and customer groups, we are committed to promoting scientific and technological progress, supporting the innovation and development of our global customers, and continuing to provide high-quality products and services to the market.

Team Introduction

The team at Kintek Solution Ltd is at the heart of the company's success. In order to realize our vision and maintain our leadership position in the field of high-tech research equipment, we are committed to building an exceptional team with the following attributes:

1. Professionalism

- **Technical Expertise:** Our team consists of technical experts and engineers in the field with deep expertise and technical backgrounds to meet complex technical challenges and innovation needs.
- **Industry experience:** We bring together professionals with extensive experience in the fields of research equipment, material science and engineering technology to ensure a precise grasp of market needs and technological trends.

2. Innovative Spirit

- **R&D-driven:** The team encourages innovative thinking and technological exploration, supports employees to participate in R&D projects on cutting-edge technologies, and continuously pushes forward the technological advancement of products and solutions.
- **Flexible Adaptation:** In the face of changing market environment, we have the ability to adapt quickly and flexibly to meet the changing needs of our customers.

3. Collaboration and Communication

- **Cross-sectoral collaboration:** The team maintains close collaboration between various departments, including R&D, production, sales and customer service, to ensure the smooth progress of projects and timely response to customer needs.
- **Efficient Communication:** Emphasize internal communication and information sharing, through efficient communication mechanisms and tools to ensure that all team members are consistent with the project goals and progress.

4. Customer Orientation

- **Customer Service:** Team members are customer-focused and committed to providing quality service and support to ensure that our customers have the best experience in using our products and solutions.

- Customized solutions: the ability to deeply understand the specific needs of customers and provide customized solutions to meet the special requirements of different customers.

5. Professional Training and Development

- Continuous Learning: We provide continuous training and learning opportunities for our team members to ensure that they are always up-to-date with the latest technology and industry knowledge.
- Career Development: We value the career development and growth of our employees, provide clear career paths and promotion opportunities, and motivate our employees to realize their personal goals and career aspirations within the company.

6. Corporate Culture

- Integrity and Responsibility: The team upholds integrity and responsibility, treats work and customers with honesty and fairness, and builds trust and long-term cooperative relationships.
- Unity and Collaboration: Focusing on the spirit of teamwork, the team emphasizes mutual support and joint efforts to achieve the company's goals and promote the overall success of the team.

By building such a highly qualified, innovation-driven and customer-oriented team, we ensure that Kintek Solution Ltd continues to lead in the field of scientific research equipment and provide excellent products and services to our customers worldwide.

At KINTEK, technology fuels our corporate spirit. This dynamic energy awaits you upon joining our team. Expect a distinctive cultural environment where our global business focus opens doors to diverse customs and traditions worldwide. Here, challenging roles promise to propel your career to new heights.

Our exceptional corporate culture sparks innovation, fosters care, and drives continuous progress among individuals and teams. Our team embodies youthfulness, positivity, enthusiasm, and a bold attitude toward challenges. Passionate about our business, our employees ardently contribute to the company's growth.

We seek individuals brave enough to embrace challenges, harbor grand ambitions, and thirst for knowledge. If you're driven by dreams and passion, and aspire to start your

entrepreneurial journey, KINTEK is the platform to actualize your career plans. We don't just offer opportunities; we pave the way for your future.

Join us at KINTEK, where innovation meets opportunity. Let's create a future that's as promising as your aspirations.

Future Plans

Kintek Solution Ltd's future plans are aimed at further strengthening our leadership position in the research equipment sector and driving the company forward in terms of technological innovation, market expansion and customer service. The following are our key future directions:

1. Technology Innovation and R&D

- **Cutting-edge technology development:** Continue to invest resources in the research and development of cutting-edge technologies, such as artificial intelligence, the Internet of Things and nanotechnology, in order to promote equipment intelligence and automation.
- **New Product Lines:** Expand existing product lines and develop equipment to meet emerging market needs, especially in the areas of biochemistry, biomedicine and high-performance materials.
- **Cooperative R&D:** Strengthen cooperation with international research institutes and institutions of higher learning to carry out joint R&D projects to ensure that the technology remains at the global leading level.

2. Market Expansion

- **Global Market Expansion:** Further expand the global market, especially in emerging markets and developing regions, establish more sales and service networks, and enhance the brand's international influence.
- **Industry application:** Explore and expand the application fields in other industries, such as new energy, environmental protection technology and intelligent manufacturing, to open up new business growth points.

3. Customer Service Enhancement

- **Enhancement of customer support:** Establish a more complete customer support system, provide 24/7 technical support and maintenance services, and ensure

the efficient experience of customers in the use of equipment.

- Customized services: Provide more customized services and solutions according to customers' individual needs to enhance customer satisfaction and loyalty.

4. Sustainable Development

- Environmentally friendly technology: Develop and adopt environmentally friendly materials and processes to reduce the environmental impact during the production and use of equipment and promote sustainable development.
- Energy saving and consumption reduction: Optimize the energy efficiency of equipment, reduce energy consumption, improve resource utilization efficiency, and support the development of green technology.

5. Internal optimization

- Intelligent management: Implement intelligent management systems and data analysis tools to improve productivity and management and reduce operating costs.
- Employee Training: Enhance employee training and skills upgrading to build a high-quality team to meet changing market demands and technological challenges.

6. Innovation ecosystem

- Establishment of innovation platform: Create innovation platforms and laboratories to support employees and partners in technological innovation and product development.
- Industry Chain Cooperation: Deepen cooperation with the upstream and downstream of the industry chain, integrate resources, and promote the development and implementation of industry technical standards and market norms.

Through these future plans, Kintek Solution Ltd will continue to lead the forefront of science and technology, provide customers with more advanced and reliable products and services, and at the same time, promote the sustainable development of the enterprise and the progress of the industry.



Slide Pecvd Tube Furnace With Liquid Gasifier Pecvd Machine

Item Number: KT-PE12



Introduction

KT-PE12 Slide PECVD System: Wide power range, programmable temp control, fast heating/cooling with sliding system, MFC mass flow control & vacuum pump.

[Learn More](#)

| | |
|------------------------------|--|
| Furnace model | KT-PE12-60 |
| Max. temperature | 1200°C |
| Constant work temperature | 1100°C |
| Furnace tube material | High purity quartz |
| Furnace tube diameter | 60mm |
| Heating zone length | 1x450mm |
| Chamber material | Japan alumina fiber |
| Heating element | Cr2Al2Mo2 wire coil |
| Heating rate | 0-20°C/min |
| Thermal couple | Build in K type |
| Temperature controller | Digital PID controller/Touch screen PID controller |
| Temperature control accuracy | ±1°C |
| Sliding distance | 600mm |
| RF Plasma unit | |
| Output Power | 5 -500W adjustable with ± 1% stability |
| RF frequency | 13.56 MHz ±0.005% stability |
| Reflection Power | 350W max. |
| Matching | Automatic |
| Noise | <50 dB |
| Cooling | Air cooling. |
| Gas precise control unit | |
| Flow meter | MFC mass flow meter |
| Gas channels | 4 channels |
| Flow rate | MFC1: 0-5SCCM O2 MFC2: 0-20SCMCH4 MFC3: 0- 100SCCM H2 MFC4: 0-500 SCCM N2 |
| Linearity | ±0.5% F.S. |

| | |
|--------------------------------|---|
| Repeatability | ±0.2% F.S. |
| Pipe line and valve | Stainless steel |
| Maximum Operating Pressure | 0.45MPa |
| Flow meter controller | Digital Knob controller/Touch screen controller |
| Standard vacuum unit(Optional) | |
| Vacuum pump | Rotary vane vacuum pump |
| Pump flow rate | 4L/S |
| Vacuum suction port | KF25 |
| Vacuum gauge | Pirani/Resistance silicon vacuum gauge |
| Rated vacuum pressure | 10Pa |
| High vacuum unit(Optional) | |
| Vacuum pump | Rotary vane pump+Molecular pump |
| Pump flow rate | 4L/S+110L/S |
| Vacuum suction port | KF25 |
| Vacuum gauge | Compound vacuum gauge |
| Rated vacuum pressure | 6x10-5Pa |

Above specifications and setups can be customized

| No. | Description | Quantity |
|-----|-------------------------|----------|
| 1 | Furnace | 1 |
| 2 | Quartz tube | 1 |
| 3 | Vacuum flange | 2 |
| 4 | Tube thermal block | 2 |
| 5 | Tube thermal block hook | 1 |
| 6 | Heat resistant glove | 1 |
| 7 | RF plasma source | 1 |
| 8 | Precise gas control | 1 |
| 9 | Vacuum unit | 1 |
| 10 | Operation manual | 1 |

Inclined Rotary Plasma Enhanced Chemical Deposition (Pecvd) Tube Furnace Machine

Item Number: KT-PE16



Introduction

Introducing our inclined rotary PECVD furnace for precise thin film deposition. Enjoy automatic matching source, PID programmable temperature control, and high accuracy MFC mass flowmeter control. Built-in safety features for peace of mind.

[Learn More](#)

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| Furnace model | PE-1600-60 |
| Max. temperature | 1600°C |
| Constant work temperature | 1550°C |
| Furnace tube material | High purity Al2O3 tube |
| Furnace tube diameter | 60mm |
| Heating zone length | 2x300mm |
| Chamber material | Japan alumina fiber |
| Heating element | Molybdenum Disilicide |
| Heating rate | 0-10°C/min |
| Thermal couple | B type |
| Temperature controller | Digital PID controller/Touch screen PID controller |
| Temperature control accuracy | ±1°C |
| RF Plasma unit | |
| Output Power | 5 -500W adjustable with ± 1% stability |
| RF frequency | 13.56 MHz ±0.005% stability |
| Reflection Power | 350W max. |
| Matching | Automatic |
| Noise | <50 dB |
| Cooling | Air cooling. |
| Gas precise control unit | |
| Flow meter | MFC mass flow meter |
| Gas channels | 4 channels |
| Flow rate | MFC1: 0-5SCCM O2 MFC2: 0-20SCMCH4 MFC3: 0- 100SCCM H2 MFC4: 0-500 SCCM N2 |
| Linearity | ±0.5% F.S. |

| | |
|---|---|
| Repeatability | ±0.2% F.S. |
| Pipe line and valve | Stainless steel |
| Maximum Operating Pressure | 0.45MPa |
| Flow meter controller | Digital Knob controller/Touch screen controller |
| Standard vacuum unit(Optional) | |
| Vacuum pump | Rotary vane vacuum pump |
| Pump flow rate | 4L/S |
| Vacuum suction port | KF25 |
| Vacuum gauge | Pirani/Resistance silicon vacuum gauge |
| Rated vacuum pressure | 10Pa |
| High vacuum unit(Optional) | |
| Vacuum pump | Rotary vane pump+Molecular pump |
| Pump flow rate | 4L/S+110L/S |
| Vacuum suction port | KF25 |
| Vacuum gauge | Compound vacuum gauge |
| Rated vacuum pressure | 6x10 ⁻⁵ Pa |
| Above specifications and setups can be customized | |

| No. | Description | Quantity |
|-----|-------------------------|----------|
| 1 | Furnace | 1 |
| 2 | Quartz tube | 1 |
| 3 | Vacuum flange | 2 |
| 4 | Tube thermal block | 2 |
| 5 | Tube thermal block hook | 1 |
| 6 | Heat resistant glove | 1 |
| 7 | RF plasma source | 1 |
| 8 | Precise gas control | 1 |
| 9 | Vacuum unit | 1 |
| 10 | Operation manual | 1 |

Plasma Enhanced Evaporation Deposition Pecvd Coating Machine

Item Number: KT-PED



Introduction

Upgrade your coating process with PECVD coating equipment. Ideal for LED, power semiconductors, MEMS and more. Deposits high-quality solid films at low temps.

[Learn More](#)

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|----------------|-----------------------|---|
| Sample holder | Size | 1-6 inches |
| | Rotate speed | 0-20rpm adjustable |
| | Heating temperature | ≤800°C |
| | Control accuracy | ±0.5°C SHIMADEN PID Controller |
| Gas purge | Flow meter | MASS FLOWMETER CONTROLLER (MFC) |
| | Channels | 4 channels |
| | Cooling method | Circulating water cooling |
| Vacuum chamber | Chamber size | φ500mm X 550mm |
| | Observation port | Full view port with baffle |
| | Chamber material | 316 Stainless steel |
| | Door type | Front open type door |
| | Cap material | 304 Stainless steel |
| | Vacuum pump port | CF200 flange |
| | Gas inlet port | φ6 VCR connector |
| Plasma power | Source power | DC power or RF power |
| | Coupling mode | Inductively coupled or plate capacitive |
| | Output power | 500W—1000W |
| | Bias power | 500v |
| Vacuum pump | Pre- pump | 15L/S Vane vacuum pump |
| | Turbo pump port | CF150/CF200 620L/S-1600L/S |
| | Relief port | KF25 |
| | Pump speed | Vane pump:15L/s□Turbo pump:1200l/s□1600l/s |
| | Vacuum degree | ≤5×10-5Pa |
| | Vacuum sensor | Ionization/resistance vacuum gauge/film gauge |
| System | Electric power supply | AC 220V /380 50Hz |

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| Rated power | 5kW |
| Dimensions | 900mm X 820mm X870mm |
| Weight | 200kg |

Rf Pecvd System Radio Frequency Plasma-Enhanced Chemical Vapor Deposition

Item Number: KT-RFPE



Introduction

RF-PECVD is an acronym for "Radio Frequency Plasma-Enhanced Chemical Vapor Deposition." It deposits DLC (Diamond-like carbon film) on germanium and silicon substrates. It is utilized in the 3-12um infrared wavelength range.

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| Equipment form | <ul style="list-style-type: none"> • Box type: the horizontal top cover opens the door, and the deposition chamber and the exhaust chamber are integrally welded; • The whole machine: the main engine and the electric control cabinet are integrated design (the vacuum chamber is on the left, and the electric control cabinet is on the right). |
| Vacuum chamber | <ul style="list-style-type: none"> • Dimensions: $\Phi 420\text{mm}$ (diameter) $\times 400\text{ mm}$ (height); made of 0Cr18Ni9 high-quality SUS304 stainless steel, the inner surface is polished, fine workmanship is required without rough solder joints, and there are cooling water pipes on the chamber wall; • Air extraction port: Double-layer 304 stainless steel mesh with 20mm front and rear intervals, anti-fouling baffle on the high valve stem, and air equalization plate at the exhaust pipe mouth to prevent pollution; • Sealing and shielding method: the upper chamber door and the lower chamber are sealed by a sealing ring to seal the vacuum, and the stainless steel network tube is used outside to isolate the radio frequency source, shielding the harm caused by radio frequency signals to people; • Observation window: Two 120mm observation windows are installed on the front and side, and the anti-fouling glass is resistant to high temperature and radiation, which is convenient for observing the substrate; • Air flow mode: the left side of the chamber is pumped by the molecular pump, and the right side is the air inflated to form a convective working mode of charging and pumping to ensure that the gas flows evenly to the target surface and enters the plasma area to fully ionize and deposit the carbon film; • Chamber material: the vacuum chamber body and the exhaust port are made of 0Cr18Ni9 high-quality SUS304 stainless steel material, the top cover is made of high-purity aluminum to reduce the weight of the top. |
| Host skeleton | <ul style="list-style-type: none"> • Made of section steel (material: Q235-A) , the chamber body and the electric control cabinet are integrated design. |
| Water cooling system | <ul style="list-style-type: none"> • Pipeline: The main inlet and outlet water distribution pipes are made of stainless steel pipes; • Ball valve: All cooling components are supplied with water separately through 304 ball valves, and the water inlet and outlet pipes have color distinctions and corresponding signs, and the 304 ball valves for the water outlet pipes can be opened and closed separately; The target, RF power supply, chamber wall, etc. are equipped with water flow protection, and there is a water cut-off alarm to prevent the water pipe from being blocked. All water flow alarms are displayed on the industrial computer; • Water flow display: The lower target has water flow and temperature monitoring, and the temperature and water flow are displayed on the industrial computer ; • Cold and hot water temperature: when the film is deposited on the chamber wall, cold water is passed through 10-25 degrees to cool the water, and it is advanced when the chamber door is opened. Pass hot water 30-55 degrees warm water. |
| Control cabinet | <ul style="list-style-type: none"> • Structure: vertical cabinets are adopted, the instrument installation cabinet is a 19-inch international standard control cabinet, and the other electrical component installation cabinet is a large panel structure with a rear door; • Panel: The main electrical components in the control cabinet are all selected from manufacturers that have passed CE certification or ISO9001 certification. Install a set of power sockets on the panel; • Connection method: the control cabinet and the host are in a conjoined structure, the left side is the room body, the right side is the control cabinet, and the lower part is equipped with a dedicated wire slot, high and low voltage, and the RF signal is separated and routed to reduce interference; • Low-voltage electrical: French Schneider air switch and contactor to ensure reliable power supply of equipment; • Sockets: Spare sockets and instrumentation sockets are installed in the control cabinet. |

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| Ultimate vacuum | <ul style="list-style-type: none"> • Atmosphere to 2×10^{-4} Pa \leq 24 hours, (at room temperature, and the vacuum chamber is clean). |
| Restore vacuum time | <ul style="list-style-type: none"> • Atmosphere to 3×10^{-3} Pa \leq 15 min (at room temperature, and the vacuum chamber is clean, with baffles, umbrella stands, and no substrate). |
| Pressure rise rate | <ul style="list-style-type: none"> • $\leq 1.0 \times 10^{-1}$ Pa/h |
| Vacuum system configuration | <ul style="list-style-type: none"> • The composition of the pump set: backing pump BSV30 (Ningbo Boss) + Roots pump BSJ70 (Ningbo Boss) + molecular pump FF-160 (Beijing); • Pumping method: pumping with soft pumping device (to reduce the pollution to the substrate during pumping); • Pipe connection: the vacuum system pipe is made of 304 stainless steel, and the soft connection of the pipe is made of; • Metal bellows; each vacuum valve is a pneumatic valve; • Air suction port: In order to prevent the membrane material from polluting the molecular pump during the evaporation process and improve the pumping efficiency, a movable isolation plate that is easy to disassemble and clean is used between the air suction port of the chamber body and the working room. |
| Vacuum system measurement | <ul style="list-style-type: none"> • Vacuum display: three lows and one high (3 groups of ZJ52 regulation + 1 group of ZJ27 regulation); • High-vacuum gauge: ZJ27 ionization gauge is installed on the top of the pumping chamber of the vacuum box near the working chamber, and the measuring range is 1.0×10^{-1} Pa to 5.0×10^{-5} Pa; • Low-vacuum gauges: one set of ZJ52 gauges is installed on the top of the pumping chamber of the vacuum box, and the other set is installed on the rough pumping pipe. The measuring range is $1.0 \times 10^{+5}$ Pa to 5.0×10^{-1} Pa; • Working regulation: CDG025D-1 capacitive film gauge is installed on the chamber body, and the measuring range is 1.33×10^{-1} Pa to $1.33 \times 10^{+2}$ Pa, vacuum detection during deposition and coating, used in conjunction with constant vacuum butterfly valve use. |
| Vacuum system operation | <p>There are two modes of vacuum manual and vacuum automatic selection;</p> <ul style="list-style-type: none"> • Japan Omron PLC controls all the pumps, the action of the vacuum valve, and the interlocking relationship between the work of the inflation stop valve to ensure that the equipment can be automatically protected in case of misoperation; • High valve, low valve, pre-valve, high valve bypass valve, in-position signal is sent to PLC control signal to ensure more comprehensive interlock function; • The PLC program can carry out the alarm function of each fault point of the whole machine, such as air pressure, water flow, door signal, over-current protection signal, etc. and alarm, so that the problem can be found quickly and conveniently; • The 15-inch touch screen is the upper computer, and the PLC is the lower computer monitoring and control valve. Online monitoring of each component and various signals are sent back to the industrial control configuration software in time for analysis and judgment, and recorded ; • When the vacuum is abnormal or the power is cut off, the molecular pump of the vacuum valve should return to the closed state. The vacuum valve is equipped with an interlock protection function, and the air inlet of each cylinder is equipped with a cut-off valve adjustment device, and there is a position set the sensor to display the closed state of the cylinder; |
| Vacuum test | <ul style="list-style-type: none"> • According to the general technical conditions of GB11164 vacuum coating machine. |



Kintek Solution

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